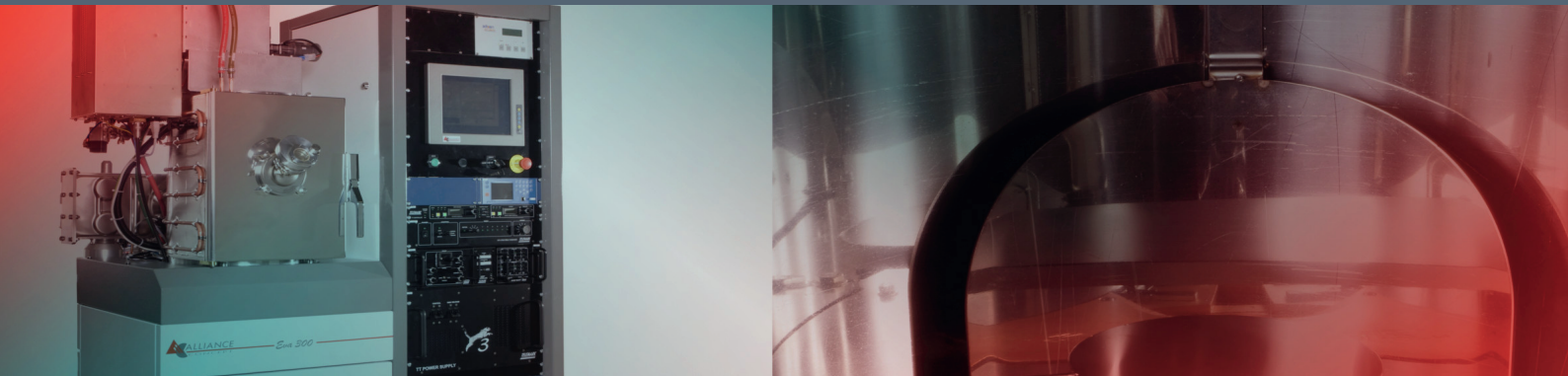


Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



Compact, modular design Evaporation - Sputtering system

EVA300



by
allianceconcept

Compact vacuum evaporator

With low footprint and high performances, this equipment guarantees the quality of your process research at low-cost effective price !

This box coating chamber is very well adapted either for magnetron sputtering or evaporation processes. Large pumping configuration allows to reduce pumping time in order to optimize system throughput.

Sources like eb-gun, thermal sources, magnetron are available in the numbers of configuration we propose. The global system is automatically and safely controlled by our PLC controller.



Main features

Vacuum chamber diameter :	300 mm
Height :	450 mm
Volume :	60 litres
Ultimate vacuum (turbopump + rough pump) :	5.10^{-7} mbar ^[1]
Ultimate vacuum (turbopump + dry unit) :	$<1.10^{-7}$ mbar ^[1]
System capacity :	4 x dia. 100 mm
Uniformity :	$< +/- 5\%$ ^[1]
Transfer load lock :	No
System controller :	Semi-automatic

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

